

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

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| INFORMATION DISCLOSURE STATEMENT | | Docket Number 2345/209 | |
| Application Number Unassigned 10/541480 | Filing Date Herewith | Examiner Unassigned | Art Unit Unassigned |
| Title INCREASING THE RESISTANCE OF CRYSTALS TO OPTICAL DAMAGE | | Applicant(s) Karsten BUSE et al. | |

Commissioner for Patents
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Mail Stop PCT

1. In accordance with the duty of disclosure under 37 C.F.R. § 1.56 and in conformance with the procedures of 37 C.F.R. §§ 1.97 and 1.98 and M.P.E.P. § 609, attorneys for Applicants hereby bring the reference(s) listed on the attached modified PTO form 1449 to the attention of the Examiner. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.
2. A copy of each patent, publication or other information listed on the modified PTO form 1449 is enclosed, except as otherwise indicated.

Dated: July 5, 2005

By: [Signature]
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| INFORMATION DISCLOSURE STATEMENT BY APPLICANT PTO-1449 | ATTY. DOCKET NO. 2345/209 | SERIAL NO. 10/541480 <i>Unassigned</i> |
| | APPLICANT Karsten BUSE et al. | |
| | FILING DATE Herewith | GROUP Unassigned |

U. S. PATENT DOCUMENTS

| EXAMINER INITIAL | PATENT NUMBER | PATENT DATE | INVENTOR NAME(S) |
|---------------------|---------------------|----------------|------------------|
| /RK/ | * US 2002/088966 A1 | July 11, 2002 | Harold Stoll |
| | | | |

FOREIGN PATENT DOCUMENTS

| EXAMINER INITIAL | DOCUMENT NUMBER | DISCLOSURE DATE | COUNTRY | TRANSLATION |
|---------------------|--------------------|-------------------|---------|-------------|
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| | | | | |

*Cited by International Searching Authority (copy to be provided by International Searching Authority to the U.S. Patent Office)

OTHER DOCUMENTS

| EXAMINER INITIAL | AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC. |
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| EXAMINER | /Robert Kunemund/ | DATE CONSIDERED | 05/07/2008 |
| EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | |

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